

Notice of References Cited	Application/Control No. 10/024,391	Applicant(s)/Patent Under Reexamination WATANABE ET AL.	
	Examiner Binh X Tran	Art Unit 1765	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,037,189	03-2000	Goto, Katsuhiko	438/31
	C	US-5,452,315	09-1995	Kimura et al.	372/46
	D	US-5,441,912	08-1995	Tsukiji et al.	438/40
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	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

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	U	Sadao Adachi, "Chemical Etching of InGaAsP/InP DH Wafer", Journal of the Electrochemical Society. vol. 129, March 1982, pages 1053-1062.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.